

Supplementary Materials: Adsorption of Titanium Halides on Nitride and Oxide Surfaces During Atomic Layer Deposition: A DFT Study

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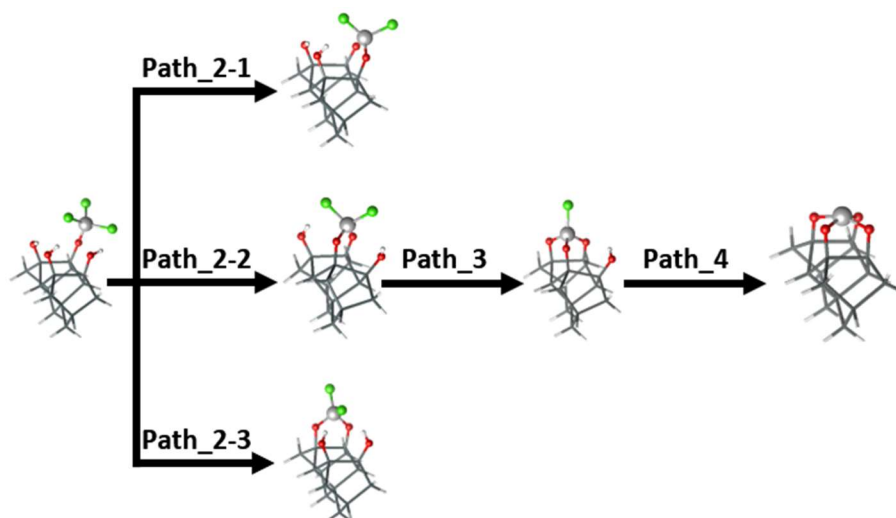


Figure S1. Multiple pathways of TiX_4 adsorption on the $-\text{OH}$ terminated Si surface.

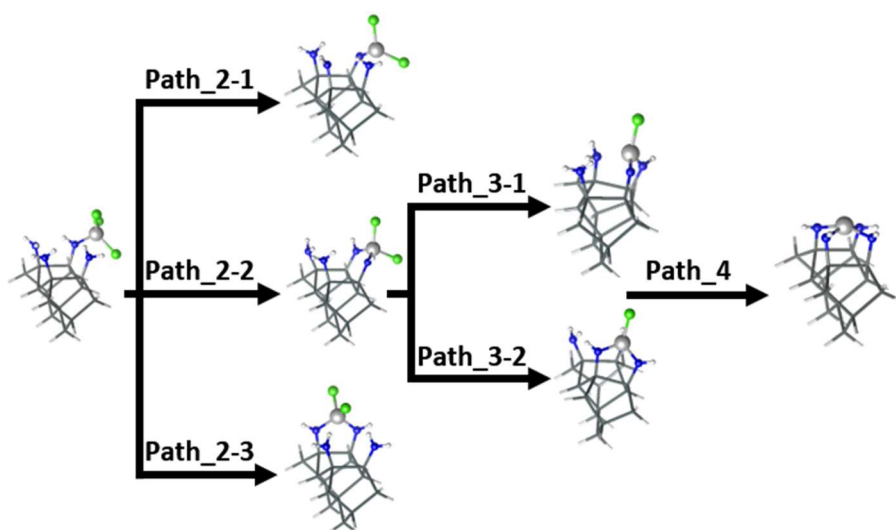


Figure S2. Multiple pathways of TiX_4 adsorption on the $-\text{NH}_2$ terminated Si surface.